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(FILE 'HOME' ENTERED AT 12:54:16 ON 14 MAY 2003)

FILE 'CA' ENTERED AT 12:54:21 ON 14 MAY 2003

L1 40433 S PROPIONATE
L2 86 S PROPIONATE
L3 40479 S L1 OR L2
L4 40 S L1 AND L2

FILE 'REGISTRY' ENTERED AT 12:55:00 ON 14 MAY 2003

L5 1 S L1 AND L2
L6 0 S TRIPROPIONATE
L7 110 S TRIPROPIONATE
L8 1 S TRIETHANOLAMINE TRIPROPIONATE
L9 0 S TRIETHANOLAMINE TRIPROPIONATE
L10 1 S PROPIONATE
L11 1 S PROPIONATE
L12 11511 S PROPIONATE

10-027424

STN

Database

Search

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Search

Notes

Keep in file

IT Kinetics of reduction
 (of cobalt superoxo complexes, by cobalt bi- and terpyridine and phenanthroline complexes)

IT Kinetics of exchange reaction
 (self-, for bond oxygen in cobalt ammine superoxo and cobalt cyano superoxo complexes)

IT Ammines
 RL: USES (Uses)
 (cobalt, reactions of dioxygen-bridged)

IT Electric potential
 (redn., of cobalt ammine superoxo and cobalt cyano superoxo complexes)

IT 15878-95-2 16788-34-4 18308-16-2
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (redn. by, of cobalt ammine superoxo and cobalt cyano superoxo complexes, kinetics of)

IT 12259-09-5 12374-80-0 12381-36-1
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (redn. of, by cobalt pyridine-deriv. and phenanthroline complexes, kinetics of)

L4 ANSWER 19 OF 19 CA COPYRIGHT 2003 ACS

AN 89:181746 CA

TI The effect of reynolds number on the collection efficiency of model grid filters

AU Fan, K. C.; Wamsley, B. T.; Furman, M.; Mooney, W.; Gentry, J. W.

CS Univ. Maryland, College Park, MD, USA

SO AIChE Symposium Series (1978), 74(175), 2-9
 CODEN: ACSSCQ; ISSN: 0065-8812

DT Journal

LA English

CC 48-7 (Unit Operations and Processes)

AB Pressure drop and collection efficiencies across model grid filters were measured as a function of the flow rate, particle size, and gas compn. Data indicate that the pressure drop is correlated by the Fuchs-Stechkina equation with a Happel flow field. Electron micrographs indicate that channeling of the flow between aligned filters occur.

ST grid filter efficiency Reynolds number; pressure drop grid filter

IT Pressure drop
 (across grid filter, detn. of)

IT Reynolds number
 (collection efficiency of grid filter in relation to)

IT Filters and Filtration apparatus
 (grid, collection efficiency of, effect of Reynolds no. on)

=> log y

COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	80.05	80.26
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE	TOTAL
	ENTRY	SESSION
CA SUBSCRIBER PRICE	-12.40	-12.40

STN INTERNATIONAL LOGOFF AT 09:30:17 ON 14 MAY 2003

L4 ANSWER 61 OF 67 CA COPYRIGHT 2003 ACS
 AN 119:128419 CA
 TI High-sensitivity photopolymerizable composition useful for lithographic plate, photoresist, and transfer sheet
 IN Kondo, Shunichi; Umehara, Akira; Aotani, Norimasa; Yamaoka, Tsugio
 PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 21 pp.
 CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM G03F007-027

ICS G03F007-00; G03F007-027; G03F007-029; G03F007-032; H01L021-027; H05K003-00

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

FAN.CNT 1

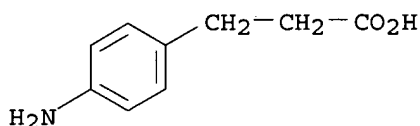
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04330445	A2	19921118	JP 1991-17331	19910208
PRAI	JP 1991-17331		19910208		
AB	The title compn. comprises (a) a cationically polymerizable compd. $R[O(R1O)nHC:CH2]n$ or $R2[COOR1OHC:CH2]n$ [R, R2 = polyalc. residue; R1 = C1-10 alkylene; n = 0, 1; and m = 2-6], (b) a compd. generating an acid upon irradiation of active ray, and (c) a solvent or an alk. sol. polymer. The compn. shows high sensitivity over UV to visible regions and its polymn. can not be suppressed with ambient O.				
ST	photopolymerizable compn lithog plate; photoresist photopolymerizable compn; transfer sheet photopolymerizable compn				
IT	Lithographic plates (manuf. of, photopolymerizable compns. for)				
IT	Photoimaging compositions and processes (polymerizable, sensitive over UV to visible regions)				
IT	Resists (photo-, photopolymerizable)				
IT	Printing, nonimpact (sheets, transfer, photopolymerizable compns. for)				
IT	99-90-1, p-Bromoacetophenone 661-20-1D, Isocyanate, reaction product with triethylene glycol monovinyl ether 757-46-0 929-72-6, Triethylene glycol vinyl ether 929-72-6D, Triethylene glycol monovinyl ether, reaction product with isocyanate 2923-28-6 57758-90-4 137308-86-2 137308-90-8 137309-10-5 137309-17-2 137309-29-6				
RL	USES (Uses) (photopolymerizable compns contg., sensitive over UV to visible regions)				

L4 ANSWER 56 OF 67 CA COPYRIGHT 2003 ACS
 AN 120:232106 CA
 TI Positive-working radiation-sensitive resin compositions
 IN **Yamaoka, Tsugio**; Murata, Makoto; Isamoto, Yoshitsugu; Miura,
 Takao
 PA Japan Synthetic Rubber Co Ltd, Japan
 SO Jpn. Kokai Tokkyo Koho, 10 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 IC ICM G03F007-039
 ICS G03F007-004; H01L021-027
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
 Reprographic Processes)
 Section cross-reference(s): 76

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05265213	A2	19931015	JP 1992-91453	19920318
PRAI	JP 1992-91453		19920318		
AB	<p>The title compns. comprise a polymer having phenolic OH groups the H atoms of which are substituted partially or wholly with a group CH₂:CROZ (R = H, C1-4 alkyl; Z = C2-4 alkylene) and a compd. which generates acid by irradiation. The compns. are useful as pos.-working resists showing high sensitivity and giving high resolution patterns with good profile and developability. A resist comprising triphenylsulfoniumtrifluoromethane sulfonate and a reaction product of polyhydroxystyrene and chloroethyl vinyl ether gave a submicron pattern by using excimer laser.</p>				
ST	photoresist compn				
IT	Phenolic resins, uses				
	RL: USES (Uses)				
	(novolak, vinyloxyalkyl ether, photoresist using)				
IT	Resists				
	(photo-, pos.-working, contg. polymer having phenolic hydroxy group etherified with vinyloxyalkyl group)				
IT	110-75-8D, ether with hydroxy group-contg. polymer 27029-76-1D, m-Cresol-p-cresol-formaldehyde copolymer, vinyloxyalkyl ether 59269-51-1D, Poly(hydroxy styrene), vinyloxyalkyl ether				
	RL: USES (Uses)				
	(photoresist using)				

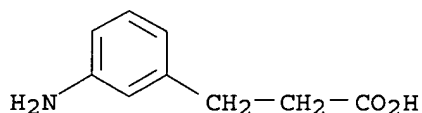
L1 ANSWER 4 OF 7 REGISTRY COPYRIGHT 2003 ACS
 RN 2393-17-1 REGISTRY
 CN Benzenepropanoic acid, 4-amino- (9CI) (CA INDEX NAME)
 OTHER CA INDEX NAMES:
 CN Hydrocinnamic acid, p-amino- (6CI, 7CI, 8CI)
 OTHER NAMES:
 CN .beta.-(4-Aminophenyl)propionic acid
 CN 3-(4-Aminophenyl)propionic acid
 CN 3-(p-Aminophenyl)propionic acid
 CN 4-Aminobenzenepropanoic acid
 CN **4-Aminohydrocinnamic acid**
 CN **p-Aminohydrocinnamic acid**
 FS 3D CONCORD
 MF C9 H11 N O2
 CI COM
 LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, CSCHEM, IFICDB, IFIPAT, IFIUDB, TOXCENTER, USPAT2, USPATFULL
 (*File contains numerically searchable property data)
 Other Sources: EINECS**
 (**Enter CHEMLIST File for up-to-date regulatory information)



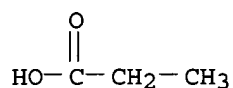
****PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT****

76 REFERENCES IN FILE CA (1957 TO DATE)
 2 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
 77 REFERENCES IN FILE CAPLUS (1957 TO DATE)
 9 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L1 ANSWER 5 OF 7 REGISTRY COPYRIGHT 2003 ACS
 RN 1664-54-6 REGISTRY
 CN Benzenepropanoic acid, 3-amino- (9CI) (CA INDEX NAME)
 OTHER CA INDEX NAMES:
 CN Hydrocinnamic acid, m-amino- (7CI, 8CI)
 OTHER NAMES:
 CN .beta.-(3-Aminophenyl)propionic acid
 CN 3-(3-Aminophenyl)propionic acid
 CN 3-Aminobenzenepropanoic acid
 CN **3-Aminohydrocinnamic acid**
 FS 3D CONCORD
 MF C9 H11 N O2
 CI COM
 LC STN Files: ANABSTR, BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CSCHEM, EMBASE, IFICDB, IFIPAT, IFIUDB, MEDLINE, PHAR, TOXCENTER, USPATFULL
 (*File contains numerically searchable property data)



L5 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS
 RN 17203-66-6 REGISTRY
 CN Propanoic acid, calcium lead(2+) salt (6:2:1) (9CI) (CA INDEX NAME)
 OTHER CA INDEX NAMES:
 CN Calcium lead propionate (Ca₂Pb(C₃H₅O₂)₆) (6CI)
 CN Propionic acid, calcium lead(2+) salt (6:2:1) (8CI)
 OTHER NAMES:
 CN Calcium lead propionate (2:1:6)
 CN Dicalcium hexapropionatoplumbate
 CN Dicalcium lead hexapropionate
 CN Dicalcium lead hexapropionate
 CN Dicalcium lead propionate
 CN Dicalcium lead propionate (Ca₂Pb(C₃H₅O₂)₆)
 CN Dicalcium lead(2+) propionate
 CN Dicalcium lead(II) propionate
 CN Lead dicalcium propionate
 DR 55198-44-2
 MF C₃ H₆ O₂ . 1/3 Ca . 1/6 Pb
 LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, GMELIN*, TOXCENTER
 (*File contains numerically searchable property data)
 CRN (79-09-4)

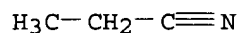


1/3 Ca

1/6 Pb(II)


68 REFERENCES IN FILE CA (1957 TO DATE)
 4 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
 68 REFERENCES IN FILE CAPLUS (1957 TO DATE)
 2 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L2 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS
 RN 107-12-0 REGISTRY
 CN Propanenitrile (9CI) (CA INDEX NAME)
 OTHER CA INDEX NAMES:
 CN Propionitrile (8CI)
 OTHER NAMES:
 CN **Cyanoethane**
 CN Ether cyanatus
 CN Ethyl cyanide
 CN Hydrocyanic ether
 CN n-Propanenitrile
 CN Propionic nitrile
 CN Propiononitrile
 CN Propylnitrile
 FS 3D CONCORD
 MF C3 H5 N
 CI COM
 LC STN Files: AGRICOLA, ANABSTR, AQUIRE, BEILSTEIN*, BIOBUSINESS, BIOSIS,
 BIOTECHNO, CA, CANCERLIT, CAOLD, CAPLUS, CASREACT, CBNB, CEN, CHEMCATS,
 CHEMINFORMRX, CHEMLIST, CHEMSAFE, CIN, CSCHEM, CSNB, DDFU, DETHERM*,
 DIPPR*, DRUGU, EMBASE, ENCOMPLIT, ENCOMPLIT2, ENCOMPPAT, ENCOMPPAT2,
 HODOC*, HSDB*, IFICDB, IFIPAT, IFIUDB, MEDLINE, MRCK*, MSDS-OHS,
 NAPRALERT, NIOSHTIC, PDLCOM*, PROMT, RTECS*, SPECINFO, SYNTHLINE,
 TOXCENTER, USPAT2, USPATFULL, VTB
 (*File contains numerically searchable property data)
 Other Sources: DSL**, EINECS**, TSCA**
 (**Enter CHEMLIST File for up-to-date regulatory information)



****PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT****

3385 REFERENCES IN FILE CA (1957 TO DATE)
 44 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
 3387 REFERENCES IN FILE CAPLUS (1957 TO DATE)
 9 REFERENCES IN FILE CAOLD (PRIOR TO 1967)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**

58 REFERENCES IN FILE CA (1957 TO DATE)

2 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA

58 REFERENCES IN FILE CAPLUS (1957 TO DATE)

1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L1 ANSWER 1 OF 1 CA COPYRIGHT 2003 ACS
 AN 94:217579 CA
 TI Photoimaging sheets
 PA Ricoh Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 IC G03C001-72; G03C001-76; G03C005-00
 CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic Processes)
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 55156938	A2	19801206	JP 1979-64003	19790525 <--
PRAI	JP 1979-64003		19790525		

AB A transparent (or semitransparent) porous support is coated with a compn. contg. a leuco dye and a biimidazole compd. on 1 side and then coated with a photosensitive compn. contg. a quinone deriv. and a proton donor on the other side to give a photoimaging sheet. Thus, a compn. consisting of bis(4-diethylamino-o-tolyl)(4-diethylaminophenyl)methane 48.5, 2,2'-bis(o-chlorophenyl)-4,4',5,5'-tetraphenylbiimidazole 132, p-toluenesulfonic acid monohydrate 38, polyethylene glycol 300 mg, cellulose acetate butyrate 1g, and Me2CO 10 mL was coated on a porous thin paper support and subsequently the backside of the support was coated with a compn. contg. p-benzoquinone 10 mg, cellulose acetate 1 g, Me2CO 9, 2-propanol 1, and triethanolamine triacetate 0.4 mL to give a photoimaging sheet. The sheet was imagewise exposed to a W lamp, then the photosensitive layer was covered with a polyester film, the sheet was heated at 100.degree., and uniformly exposed to a UV light to give blue-pos. images in the recording layer.
 ST photothermog sheet photofixing type
 IT Photothermography
 (photofixing type photosensitive sheets for)
 IT 68582-45-6
 RL: USES (Uses)
 (photofixing type photothermog. sheet contg.)
 IT 71-23-8, uses and miscellaneous 80-39-7 104-15-4, uses and miscellaneous 106-51-4, uses and miscellaneous 110-16-7, uses and miscellaneous 130-15-4 1707-68-2 3002-18-4 4482-70-6 9002-89-5 9004-36-8
 RL: USES (Uses)
 (photofixing type photothermog. sheets contg.)